

ELECTROSTATIC CHUCK AND PLASMA PROCESSING APPARATUS

ABSTRACT

An electrostatic chuck includes a substrate support to support at least one of a substrate or
5 an edge ring, an electrostatic electrode inside the substrate support to electrostatically clamp at
least one of the substrate or the edge ring, and an electrode inside the substrate support and
located on a plane different from a plane on which the electrostatic electrode is located. The
substrate support has a through-hole extending through the substrate support from an upper
surface of the substrate support to a lower surface of the substrate support. The electrode is at
10 least partially located between the electrostatic electrode and the through-hole.

[FIG. 4]